

ABSTRACT

A novel polymer is obtained by copolymerizing a
5 (meth)acrylic acid derivative with a vinyl ether compound,
an allyl ether compound and an oxygen-containing alicyclic
olefin compound. A resist composition comprising the
polymer as a base resin is sensitive to high-energy
radiation, has excellent sensitivity, resolution, etching
10 resistance, and minimized swell and lends itself to
micropatterning with electron beams or deep-UV.

TOP SECRET - SOURCE CODE